CHM 165,265 / BIMM 162 / BGGN 262 Spring 2013

Lecture Slides

Jan 17, 2013

P-Flasher Question

Which of the following is designed to act as an electrostatic lens in the TEM?

- A. Objective aperture
- B. Objective lens
- C. Specimen stage
- D. Wehnelt shield
- E. Second condenser lens

P-Flasher Question

In the TEM, the specimen is situated very close to the front focal plane of the objective lens on the side closer to the center of the lens field.

A. TrueB. False

P-Flasher Question

The final image formed on the viewing screen or photographic emulsion is a virtual one and only becomes a real one when we view the screen or micrograph with our eyes.

A. TrueB. False

CHM 165,265 / BIMM 162 / BGGN 262 Spring 2013 Announcements for Jan 17, 2013

Reading assignment for Tuesday: Lecture notes pp.81-103 'Virtual homework': always check web site for new updates Recitation session: Tomorrow at 5-6:00 pm in York 4080A TEM facility tour: Jan 28,29 (check web site) Reminders:

Keep your *p-Flasher* sheets readily available during class

Powerpoint lectures posted on Web site will include additional ('hidden') slides not shown during class



CHM 165,265 / BIMM 162 / BGGN 262 Winter 2013 3D Electron Microscopy of Macromolecules

TEM Facility Tour

Where: 1510 Bonner Hall basement

When: Mon Jan 28 and Tue Jan 29th

Check class web site for details on dates, times, and directions to facility

Attendance is optional but 5 pts extra credit towards final grade will be awarded



FEI Technai Sphera (200keV; LaB₆; LN₂)

To reserve and guarantee a time slot, email **nholson@ucsd.edu First come, first served.**

Class Web Page: Jan 16, 2013

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> CHEM 165,265 / BIMM 162 / BGGN 262 - 3D Electron Microscopy of Macromolecules Winter Quarter 2013



Class Tour of the Electron Microscopy Facility Bonner Hall 1501

Sign-up times: Monday, January 28 -- 1 pm to 2 pm Monday, January 28 -- 2 pm to 3 pm Monday, January 28 -- 3 pm to 4 pm Tuesday, January 29 -- 10 am to 11 am Tuesday, January 29 -- 1 pm to 2 pm Tuesday, January 29 -- 2 pm to 3 pm Tuesday, January 29 -- 3 pm to 4 pm

To reserve a demo session write: <u>Norm Olson</u> (Only four participants allowed per session - first come-first served) (Keep an eye on this page. Closed sessions will be in red strikeout text)

Directions to the EM Facility

Syllabus (PDF)

Book list (PDF)

Reference list (PDF)

The Bottom Line (PDF) -- Key concepts from daily lectures through January 15, 2013

Virtual Homework - Practice Questions for Section I (PDF) Updated January 15, 2013 (Password protected)

Lecture Notes

- Sec. IA. Principles of the transmission electron microscope (9.2 MB)
- Sec. IB. Design of the transmission electron microscope (3.5 MB)
- Sec. IC. Contrast and image formation (692 KB)

Powerpoint® presentations from lecture (PDFs)

- Introduction to the course January 8, 2013 (48 MB)
- Lecture #1 January 8, 2013 (15.5 MB)
- Lecture #2 January 10, 2013 (4.3 MB)
- Lecture #3 January 15, 2013 (20.8 MB)

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KEY CONCEPTS FROM LECTURE #3

- Thermionic emission creates a source of electrons
- Electrons passing through an electric or a magnetic field are bent or refracted
- Focal length of electromagnetic lens determined by field strength and by electron speed

$$f = \frac{KV_r}{\left(N \cdot I\right)^2}$$

- Wehnelt shield (gun cap) controls beam shape and emission in the e⁻ gun
- Gun-crossover considered the actual source of electrons for the TEM
- Double condenser lens system focuses / concentrates the electron beam onto the specimen (gives optimal illumination for viewing and recording images)
- Smaller **condenser apertures** increase coherence of the electron beam and hence, phase-contrast effects in electron images

MORE KEY CONCEPTS FROM LECTURE #3

- Electromagnetic lenses are 'crummy': they are reason why resolving power is much worse than estimated according to the simple $1/2 \lambda$ criteria
- Spherical aberration (of objective lens): main culprit and the principal factor limiting resolving power in the TEM
- Chromatic aberration: lens focal length varies with electron/photon wavelength; images with CA are blurred (superposition of a series of images with different focal planes, rotations, and magnifications)
- Lens asymmetry: no real lens can be manufactured that is perfectly axially symmetric. Result: focal length varies with direction. Condenser and objective lens astigmatism are controlled (i.e minimized) by the microscopist.
- Objective lens: most critical lens of TEM; performs 1st stage of imaging and determines instrument resolving power and image contrast
- Objective aperture: at <u>back focal plane</u> of the objective lens; intercepts electrons scattered by the specimen through large angles

The TEM Top to Bottom:

- Electron gun
- Condenser lens(es)
- Lens aberrations
- Objective lens and specimen stage
- Projector lenses
- Camera and viewing system
- Vacuum system
- Electrical system





§ I: The Microscope

I.B Design of the TEM

I.B.4 Objective Lens and Specimen Stage

(pp.54-62 of lecture notes)



Specimen holder

Objective lens Objective lens aperture

I.B.4 Objective Lens and Specimen Stage

Bottom Line:

Objective lens is the **most critical** lens in the TEM

- Performs first stage of imaging
- Determines instrument resolving power and image contrast

I.B.4 Objective Lens and Specimen Stage I.B.4.b Objective Lens Construction



I.B.4 Objective Lens and Specimen Stage I.B.4.b Objective Lens Construction Main Requirements

- Specimen situated close to and before the front focal plane of the objective lens
- Specimen sits *inside* the lens field (necessary to obtain short focal length)
- Space is very cramped (need adequate clearance for inserting several items):
 Specimen
 - Aperture
 - Anticontaminator
 - Stigmators to correct for asymmetries in the lens field

Specimen holder



FUNCTION: Intercepts electrons scattered by the specimen through large angles

POSITION: Right at the *back focal plane* of the objective lens

Schematic of lengthwise section through objective lens pole pieces



OA does not restrict field of view

From Wischnitzer 2nd ed., Fig. 51, p.60

FUNCTION: Intercepts electrons scattered by the specimen through large angles

POSITION: Right at the *back focal plane* of the objective lens

Here, the OA screens out widely scattered electrons from being imaged



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POSITION: Right at the *back focal plane* of the objective lens

Here, the OA screens out widely scattered electrons from being imaged



I.B.4 Objective Lens and Specimen Stage I.B.4.e Objective Aperture (OA) *Miscellaneous Factoids:*

- Hole diameter generally ~ 25-75 μm
- Must be perfectly circular and clean

A 'dirty' aperture will distort the imaging field

Will act like a weak electrostatic lens and cause image astigmatism

I.B.4 Objective Lens and Specimen Stage I.B.4.e Objective Aperture (OA) *Miscellaneous Factoids:*

- Hole diameter generally ~ 25-75 μ m
- Must be perfectly circular and clean (or imaging field will be distorted) Contaminated aperture can act like a weak electrostatic lens and cause image astigmatism
- Ultrathin, self-cleaning metal apertures are best
- Smallest apertures give best image contrast but exhibit more serious contamination effects



Desirable Properties of a Specimen Stage

- Specimen exchange should be simple and rapid
- Must have a specimen **airlock**
- Should sit in a plane that is well defined with respect to its position along the axis of the optical system
- Provide **minimum mechanical backlash, drift,** and **vibrations**, and minimal thermal motions and other movements

See p.59 of lecture notes for additional properties

How do I get the sample into the TEM?

Microscopes come in only two "flavors":

Side Entry - Most common

Top Entry

How do I get the sample into the TEM?

Side Entry







From Meek, 1st ed., Fig. 5.14, p.114

One for nearly every need!!!

- Tilt stage
- Multiple specimen stage
- Furnace heating stage
- Grid heater stage
- Cold stage
- Straining stage
- Gas reaction stage
- Hydration or 'wet' stage
- Many, many more....

See notes (p.61) for some details

One for nearly every need!!!

- Tilt stage
- Multiple specimen stage
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- Grid heater stage
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See notes (p.61) for some details

The TEM Top to Bottom:

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§ I: The Microscope

I.B Design of the TEM

I.B.5 Projector Lens(es)

(pp.62-64 of lecture notes)



I.B.5 Projector Lenses I.B.5.a Description

Projector Lens Systems

Produce and control magnification of final image

3-4 lenses (diffraction, intermediate, plus one or two projector lenses) give a wide magnification range (~1000X up to >500,000X)

Intermediate image produced by objective lens serves as object of 1st 'projector' lens, and so forth.


I.B.5 Projector Lenses

KEY CONCEPTS





Recall: A **real** lens images each object point as an **Airy disc**, the radius of which = lens resolving power



There is a finite distance along the optic axis, *D*_i, where the <u>image</u> appears essentially unchanged. This is distance is called **depth of focus**.



There is a finite distance along the optic axis, *D*_i, where the <u>image</u> appears essentially unchanged. This is distance is called **depth of focus**.



An analogous distance, *D*_o, exists along the optic axis on the **object side** over which the object **could** be moved and still give a maximally sharp image (at position of "exact" image plane). This distance is called the **depth of field**.

Decreasing the aperture of the lens *increases* **both** D_0 and D_i .



Decreasing the aperture of the lens *increases* **both** D_0 and D_i .



Decreasing the aperture of the lens *increases* **both** D_0 and D_i .



I.B.5 Projector Lenses I.B.5.c Depth of Field and Depth of Focus Depth of Field (Object/Specimen Plane)

$$D_o = \frac{2d}{\tan \alpha_o}$$

d = minimum object spacing one hopes to resolve $\alpha_0 =$ semi-angular aperture of **objective lens**

EXAMPLE: For d = 1.0 nm and $\alpha_0 = 5 \times 10^{-3}$ radians, $D_0 = 400$ nm (thicker than all macromolecules and most TEM specimens)

CONSEQUENCE: The entire 3D contents of a thin specimen appear equally sharp in 2D electron images

Depth of Focus (Image Plane)

$$D_i = \frac{M^2 2d}{\tan \alpha_o} = D_o M^2$$

- M =total magnification of the compound magnifying system
- d = minimum object spacing one hopes or expects to resolve
- α_o = semi-angular aperture of **objective lens**

EXAMPLE: If M = 50,000X, d = 1.0 nm, and $\alpha_0 = 5 \times 10^{-3}$ radians, then $D_i = 1000$ meters!!!

OK, so what the heck does this mean?

Practical Consequences

- Fluorescent screen, photographic film or CCD/DDD camera can be placed ANYWHERE on the optic axis <u>beneath</u> the projector lens and the final image will look essentially the same (but the magnification <u>DOES change</u>)
- Large depth of field or focus does <u>NOT</u> eliminate the requirement for VERY CAREFUL FOCUSING of the image (by adjusting the objective lens strength)

Ugh....just when you were beginning to think something might actually make some sense !!!

Consequence of large relative depth of field in the TEM

Images are (to a first approximation) **PROJECTIONS** of the **entire contents** of a specimen.

Each portion of the 2D image represents the projected contributions from all points in the 3D specimen in the direction of the electron beam.



IMPORTANT DISTINCTION:

Projection images are *****NOT***** shadow-graphs, where light is **not** transmitted **through** the object.



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Projection images are *****NOT***** shadow-graphs, where light is **not** transmitted **through** the object, but are **similar to X-ray photos**.



www.worth1000.com

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From Sjostrand, Fig. IV-23, p. 123

www.tegascience.co.jp/products/stn/applications/xray_20RatSkeleton.jpg

The TEM Top to Bottom:

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- Vacuum system
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§ I: The Microscope

I.B Design of the TEM

I.B.6 Camera and Viewing System

(pp.65-66 of lecture notes)

I.B.6 Camera and Viewing System I.B.6.a Viewing the Image

- Electron optical image is projected onto a fluorescent screen (coated with zinc sulfide crystals)
- Kinetic energy of electrons in the image is transformed into light energy through fluorescence
- Resolution of image seen on <u>SCREEN</u> determined by size of ZnS crystals (~50-75 μm)

I.B.6 Camera and Viewing System

I.B.6.b Recording the Image

- Photographic recording must be done at a magnification sufficient to capture resolution present in the electron image
- Electron images typically recorded on CCD camera or photographic emulsion (DDD cameras may soon replace photographic emulsions)
- Resolution of CCD: depends on pixel size, which is typically 15 μ m (*i.e.* superior to the fluorescent screen)
- Resolution of photographic emulsions: depends on size of silver halide crystals (~1-5 μm, hence >10 times better than the fluorescent screen)

NOTE: More details about recording electron images later (§ I.E10-12).

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The TEM Top to Bottom:

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§ I: The Microscope

I.B Design of the TEM

I.B.7 TEM Vacuum System

(pp.66-71 of lecture notes)

I.B.7 TEM Vacuum Systems

Bottom Line: Electron beam needs a 'free path'

- Mean free path of a moving electron in air (760 Torr) is
 < 100 nm (*i.e.* < 0.1 μm) !!!
- High vacuum essential to allow electron beam to pass through entire TEM column (> 1 meter)
- TEMs use 10⁻⁶ Torr or lower (MFP is 10s of meters)
- TEMs generate high vacuum by using two or more different type pumps in tandem

I.B.7 TEM Vacuum Systems I.B.7.b Types of Pumps

Bottom Line: A Pump for Every Need

- Rotary Vane ("Roughing") 10⁻³ to 10⁻⁴ Torr
- Diffusion 10⁻⁵ to 10⁻⁷ Torr
- Ion 10⁻⁷ to 10⁻⁹ Torr
- Turbomolecular 10⁻⁷ to 10⁻¹⁰ Torr
- Cryo 10⁻⁸ to 10⁻¹¹ Torr

NOTE: 1 atmosphere (1 atm) = 760 Torr

See lecture notes pp.66-69 for brief descriptions of each pump



I.B.7 TEM Vacuum Systems I.B.7.b Measuring Vacuum (Gauges)

Quality of the vacuum obtained by each type of pump is monitored by different type gauges:

- Thermocouple gauge
- Pirani gauge
- Ion gauge
- Penning gauge

See lecture notes pp.69-70 for brief descriptions

I.B.7 TEM Vacuum Systems Problems Caused by Poor Vacuum

Specimen contamination

Specimen etching

Decreased filament life

I.B.7 TEM Vacuum Systems

Problems Caused by Poor Vacuum

Specimen contamination:

Hydrocarbon residues from oil, grease, etc., when hit by the e⁻ beam, decompose into H and C. C atoms crosslink to the specimen, obscure details, and reduce resolution.

Specimen etching:

Residual H₂O in or near the specimen is ionized by the e⁻ beam, producing highly reactive OH⁻ ions. These attack carbon in the specimen, producing volatile CO. The specimen essentially 'burns' up in the beam.

Decreased filament life:

Filament quickly etches in a poor vacuum

I.B.7 TEM Vacuum Systems

Problems Caused by Poor Vacuum

Specimen contamination: Specimen etching:

Reduce or eliminate these two problems with an **anti-contaminator**

Device that traps contaminants before they reach the specimen

I.B.7 TEM Vacuum Systems Anticontaminator

A **cooled surface** placed close to the specimen traps residual gases in the column, preventing them from interacting unfavorably with the specimen. Most anticontaminators are cooled with **liquid N**₂.



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- Electrical system





The TEM Top to Bottom:

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- Vacuum system
- Electrical system (notes pp.71-72)



§ I: The Microscope

I.B Design of the TEM

I.B.8 TEM Electrical System

(pp.71-72 of lecture notes)

I.B.8 Electrical System

TEMs are full of electronics:

- Current to heat the filament (generate beam electrons)
- High voltage to accelerate the emitted e⁻ beam
- Current to all lenses to generate magnetic fields to focus electrons
- Power to many circuits:

Stigmators Beam deflectors Camera and camera shutter Exposure meter Focus wobbler Safety devices Relay switches Diffusion, rotary, getter pumps Microprocessor etc. etc. etc.

I.B.8 Electrical System

Bottom Line:

1. Current supplies for each lens must be very stable

Objective lens: <u>strictest stability requirement</u> (1 part in 100,000)

If current varies through <u>any</u> imaging lens, the image rotates about a point called the **current rotation center**

Any micrograph recorded *while* this happens will be **blurred**

2. Voltage should also be stable (~1 part in 50,000)

Fluctuations produce **magnification changes** (image grows or contracts radially about the **voltage center**)

Fluctuations that occur during recording of the micrograph lead to **image blurring**


TOPICS

- Principles of TEM

Electrons, lenses and optics

- Design of TEM

Components top to bottom

- Contrast and image formation Electron scattering from object
- Optimizing TEM performance Alignment assures 'best' images
- Operation of TEM "What do all these buttons do?"
- Other modes of TEM Many ways to 'observe' specimens
- Specimen preparation for TEM Getting specimen ready
- Radiation damage Less is better
- 3D reconstruction

Specimen 3D structure from 2D images

§ I: The Microscope

I.A Principles of TEM
I.B Design of the TEM
I.C Contrast and Image Formation (pp.73-80 of lecture notes)

I.C CONTRAST AND IMAGE FORMATION KEY CONCEPTS

- Specimens are made of **atoms** (mainly empty space)
- Electron beam interacts with (*i.e.* scatters from) specimen atoms
- In TEM, **image contrast** arises in two ways:

Removal of electrons by objective **aperture** (**amplitude**)

Interference of electron waves (**phase**)

I.C CONTRAST AND IMAGE FORMATION MORE CONCEPTS

- Resolution of features in <u>electron images</u> of biological specimens (or virtually any <u>thin</u> specimen) is <u>normally</u> limited by contrast BUT NOT lack of resolving power
- **RECALL: resolving <u>power</u>** of TEM: 0.2-0.3 nm (2-3 Å) Limited by optics, not by the specimen or electron λ
- Resolution limit in TEM images of biological specimens:
 <u>Generally</u> 1-5 nm (10 50 Å)
- BUT: You will soon learn that sometimes, with judicious specimen preparation and microscopy procedures, and with computer processing of images, higher resolutions CAN be achieved

I.C CONTRAST AND IMAGE FORMATION IMAGE CONTRAST IN THE TEM

Determined by two factors:

- 1. The nature and extent of **interactions** between the electron beam and the specimen
- 2. How the electron image forms

I.C CONTRAST AND IMAGE FORMATION IMAGE CONTRAST IN THE TEM

Two sources of contrast:

Specimen (inherent contrast) Microscope (instrumental contrast)

Both are important !!!

I.C CONTRAST AND IMAGE FORMATION DEFINITION: CONTRAST

The **relative** difference in intensity between an image point and its surroundings

Percent contrast =
$$100 \times \frac{\left|I_i - I_b\right|}{I_b}$$

 I_i = intensity of an image point

 I_b = intensity of the background **adjacent** to the image point

Percent contrast =
$$100 \times \frac{|I_i - I_b|}{I_b}$$

The **relative** difference in intensity between an image point and its surroundings



Percent contrast =
$$100 \times \frac{|I_i - I_b|}{I_b}$$

The **relative** difference in intensity between an image point and its surroundings



Percent contrast =
$$100 \times \frac{|I_i - I_b|}{I_b}$$

The *relative* difference in intensity between an image point and its surroundings

What about the orange disks?



I.C CONTRAST AND IMAGE FORMATION Contrast in LM vs. TEM

LM - differential **absorption** of photons - depends mainly on staining

- **EM** differential **scattering** of electrons
 - negligible absorption of electrons for "thin" specimens (*i.e.* <100-200 nm)

§ I: The Microscope

I.C Contrast and Image Formation

I.C.1 Electron Scattering

(pp.73-75 of lecture notes)

I.C.1 Electron Scattering

A few important facts:

- Amount of e⁻ scattering from a finite region of a specimen depends on the density AND overall thickness of the specimen in the direction of the beam
- Scattering probability increases as mass thickness increases
- To a *first approximation*, scattering is **independent** of chemical composition and other specimen properties





I.C.1 Electron Scattering Mass thickness = density x thickness





I.C.1 Electron Scattering Mass thickness = density x thickness



I.C.1 Electron Scattering A few more relevant facts:

Biological specimens have <u>low inherent</u> contrast (mainly composed of light atoms: H, C, O, N)

Weak contrast is a limiting problem in imaging biological specimens (or any thin specimen)

How is <u>inherent</u> contrast increased?

Add materials of **high atomic number** to the specimen (basis of most "conventional" biological specimen preparation procedures)

Consider electron beam as it passes *through* a specimen

Paths of beam electrons affected primarily by electrostatic interactions with the specimen atom components:

- Nuclei (protons + neutrons)
- Electrons

(in the electron shells or 'cloud' that surround the atomic nuclei)

Recall: Matter is primarily **empty space**

- Beam electrons must pass very close to an atomic nucleus or electron to be scattered
- Beam electrons passing beyond the range of the electrostatic fields produced by atomic nuclei and electrons are not scattered
- Rare for beam electrons to collide directly with atomic nuclei or electrons

Primary types of electron/specimen scatter:

Elastic Inelastic None

Primary types of electron/specimen scatter:

ElasticNo energy loss (no change in velocity or λ)InelasticSome energy loss (~10-20 eV per event)NoneNo energy loss

Primary types of electron/specimen scatter:

Elastic No energy loss (no change in velocity or λ)

nelastic Some energy loss (~10-20 eV per event)

- Main cause of radiation damage in biological specimens
- Velocity of imaging electron decreases (λ increases)

None No energy loss

- Significant fraction of beam electrons are unscattered after passing through a "thin" specimen

I.C.1 Electron Scattering I.C.1.a Elastic Scattering I.C.1.b Inelastic Scattering



Beam electron trajectories near specimen atom 'stationary' electron

 θ_2

 r_{e_2}

Beam electron trajectories near

specimen atom nucleus

I.C.1 Electron Scattering

I.C.1.a Elastic Scattering



I.C.1.b Inelastic Scattering



Beam electron trajectories near specimen atom nucleus

- Z = atomic number of specimen atom
- e = charge of an electron
- V = accelerating voltage of illumination beam
- r_n = distance of beam electron from specimen
 atom nucleus

Beam electron trajectories near specimen atom 'stationary' electron

*r*_e = distance of beam electron from specimen **atom electron**

From Slayter, Fig. 19-2, p. 423



I.C.1 Electron Scattering I.C.1.b Inelastic Scattering

More facts about inelastic scattering...

- Typically just one scattering event as electron passes through a specimen 'thinner' than ~100 nm (= 1000 Å)
- Each time a beam electron is inelastically scattered, it looses ~10-20
 eV of energy (*i.e.* shift to longer wavelength and lower velocity)
- 10-20 eV of energy loss <u>corresponds</u> to fluctuations in accelerating voltage of the order one part in 10⁴-10⁵
- Hence, change in λ produced by a **SINGLE** inelastic event is relatively insignificant, but does contribute to chromatic aberration
- Multiple scattering occurs in thick specimens and can be a serious source of chromatic aberration and loss of resolution



I.C.2 Amplitude/Phase Contrast

... and now (of course) the plot thickens...

Contrast in electron images arises from **scattering AND interference** effects

SCATTERING (AMPLITUDE or APERTURE) CONTRAST:

Produced by **loss of amplitude** (*i.e.* electrons) from the imaging beam (**PARTICLE nature** of electrons)

INTERFERENCE (PHASE) CONTRAST:

Originates from **shifts in relative phases** of portions of the imaging beam that combine and contribute to the image (**WAVE nature** of electrons)

SCATTERING (APERTURE) CONTRAST

Primary source of electron contrast for most biological specimens prepared for TEM using "conventional" methods (*i.e.* those stained or shadowed with heavy atoms to increase mass thickness)

INTERFERENCE (PHASE) CONTRAST

Arises primarily from two factors:

Defocusing the objective lens Spherical aberration in the objective lens

Importance of interference contrast increases as the **limit of resolution** in the TEM is approached, and for **small / thin** structures

Dominant source of contrast for very small or thin objects of low atomic number

I.C.2.a Scattering (Aperture) Contrast



Electron 'opaque' object points produce appreciable scattering of beam electrons through relatively large angles

I.C.2.a Scattering (Aperture) Contrast



Electron 'opaque' object points produce appreciable scattering of beam electrons through relatively large angles

These e⁻ are **excluded from** (*i.e.* fall outside) **the lens aperture** and don't reach the image plane

Intensity in these image points is correspondingly **low** (**I** < **I**₀)

I.C.2.a Scattering (Aperture) Contrast Io Specimen plane **Objective lens OA** Image plane $|<|_0$ **I**0

Conversely:

Electron 'transparent' regions in the object (lower average atomic number and/or mass thickness) produce little scattering outside the lens aperture

These e⁻ mostly fall **inside the lens** aperture and nearly all reach the image plane

Intensity in these image points is correspondingly high ($I \cong I_0$)

I.C.2.a Scattering (Aperture) Contrast Io Specimen plane **Objective lens** OA Image plane $| < |_0$ **I**0

<u>Aperture</u> contrast controlled to some extent by:

- Choice of accelerating voltage (contrast \uparrow as V \downarrow)



- Size of objective aperture (contrast \uparrow as aperture size \downarrow)

I.C.2.a Scattering (Aperture) Contrast



<u>Aperture</u> contrast controlled to some extent by:

 Choice of accelerating voltage (contrast ↑ as V ↓)

 $\theta_n = \frac{Ze}{Vr_n}$ $\theta_e = \frac{e}{Vr_e}$

 Size of objective aperture (contrast ↑ as aperture size ↓)

Warning:

- Lower V leads to higher chromatic aberration and loss of resolution (esp. for thicker specimens)